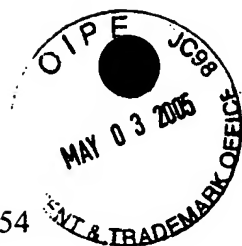


00684.003654

PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:)	
Takako YAMAGUCHI et al.)	Examiner: Unassigned
Application No.: 10/529,891)	Group Art Unit: Unassigned
Entry into U.S. National)	
Stage Under 35 U.S.C. § 371: April 1, 2005)	
For: EXPOSURE MASK, METHOD OF)	May 3, 2005
DESIGNING AND MANUFACTURING)	
THE SAME, EXPOSURE METHOD AND)	
APPARATUS, PATTERN FORMING)	
METHOD, AND DEVICE)	
MANUFACTURING METHOD)	

Mail Stop Amendment
 Commissioner for Patents
 P.O. Box 1450
 Alexandria, VA 22313-1450

INFORMATION DISCLOSURE STATEMENT

Sir:

In compliance with the duty of disclosure under 37 C.F.R. § 1.56 and in accordance with the practice under 37 C.F.R. §§ 1.97 and 1.98, the Examiner's attention is directed to the documents listed on the enclosed PTO-1449 form. Copies of the Japanese patent documents (with English language abstracts) and PCT publication are also enclosed.

U.S. Patent No. 6,171,730 is discussed on pages 2-3 of the specification.

Japanese patent document number 11-317345 and U.S. Patent No. 6,497,996 are discussed on page 3 of the subject specification. U.S. Patent No. 6,671,034 and U.S. Patent Application Publication No. 2004/0090610 A1 are English language counterparts of the '345 Japanese patent document.

U.S. Patent No. 6,171,730 B1, U.S. Patent Application Publication No. 2001/046719 A1, International Application No. WO 03/001869 A, McNab et al. "Analytic

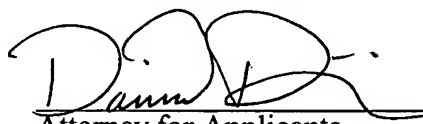
study of gratings patterned by evanescent near field optical lithography,” Luo et al.
“Surface plasmon resonant interference nanolithography technique,” and Alkaisi et al.
“Nanolithography in the Evanescent Near Field” were cited in an International Search
Report, which was mailed on September 27, 2004, from the European Patent Office in
corresponding International Application No. PCT/JP2004/009375. Copies of the
International Search Report and a Written Opinion mailed September 27, 2004 are also
enclosed.

Applicants request that the above information be considered by the Examiner and
that a copy of the enclosed PTO-1449 form be initialed and returned indicating that such
information has been considered.

This Information Disclosure Statement is being filed before the issuance of a first
Office Action on the merits. Therefore, no fee under 37 C.F.R. 1.97(c)(2) is believed due.
Nevertheless, the Commissioner may charge Deposit Account No. 06-1205, should any fee
be due for filing this paper.

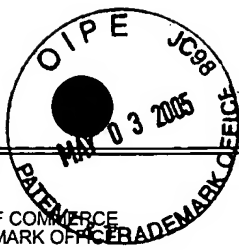
Applicants’ undersigned attorney may be reached in our Washington D.C. office
by telephone at (202) 530-1010. All correspondence should continue to be directed to our
address given below.

Respectfully submitted,



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FORM PTO 1449 (modified) U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE LIST OF REFERENCES CITED BY APPLICANT(S) (Use several sheets if necessary) May 3, 2005				ATTY DOCKET NO. 00684.003654		APPLICATION NO. 10/529,891	
APPLICANT Takako YAMAGUCHI et al.							
FILING DATE April 1, 2005						GROUP Unassigned	

U.S. PATENT DOCUMENTS							
*EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE	
	US 6,171,730 B1	01/09/2001	Kuroda et al.	430	5		
	2001/0046719 A1	11/29/2001	Yamaguchi et al.	438	11		
	2003/0129545 A1	07/10/2003	Kik et al.	430	313		
	US 6,497,996	12/24/2002	Naya et al.	430	323		
	US 6,671,034 B1	12/30/2003	Hatakeyama et al.	355	67		
	2004/0090610 A1	05/13/2004	Hatakeyama et al.	355	67		

FOREIGN PATENT DOCUMENTS							
DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION YES/NO/ OR ABSTRACT		
11-317345	11/16/1999	Japan			Abstract		
WO 03/001869 A2	01/09/2003	PCT					

OTHER DOCUMENT(S) (Including Author, Title, Date, Pertinent Pages, Etc.)	
	International Search Report mailed September 27, 2004, issued in corresponding International Application No. PCT/JP2004/09375.
	Written Opinion mailed September 27, 2004, issued in International Application No. PCT/JP2004/09375.
	McNab, S. J., et al., "Analytic study of gratings patterned by evanescent near field optical lithography," J. Vac. Sci. Technol. B 18(6), Nov/Dec 2000, pp. 2900-2904.
	Luo, Xiangang, et al., "Surface plasmon resonant interference nanolithography technique," Applied Physics Letters, Vol. 84, No. 23, June 7, 2004, pp. 4780-4782.
	Alkaisi, Maan M., et al., "Nanolithography in the Evanescent Near Field," Advanced Materials, 13, No. 12-13, July 4, 2001, pp. 877-887.

EXAMINER	DATE CONSIDERED
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*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.